

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL

VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DVIC1

1/6

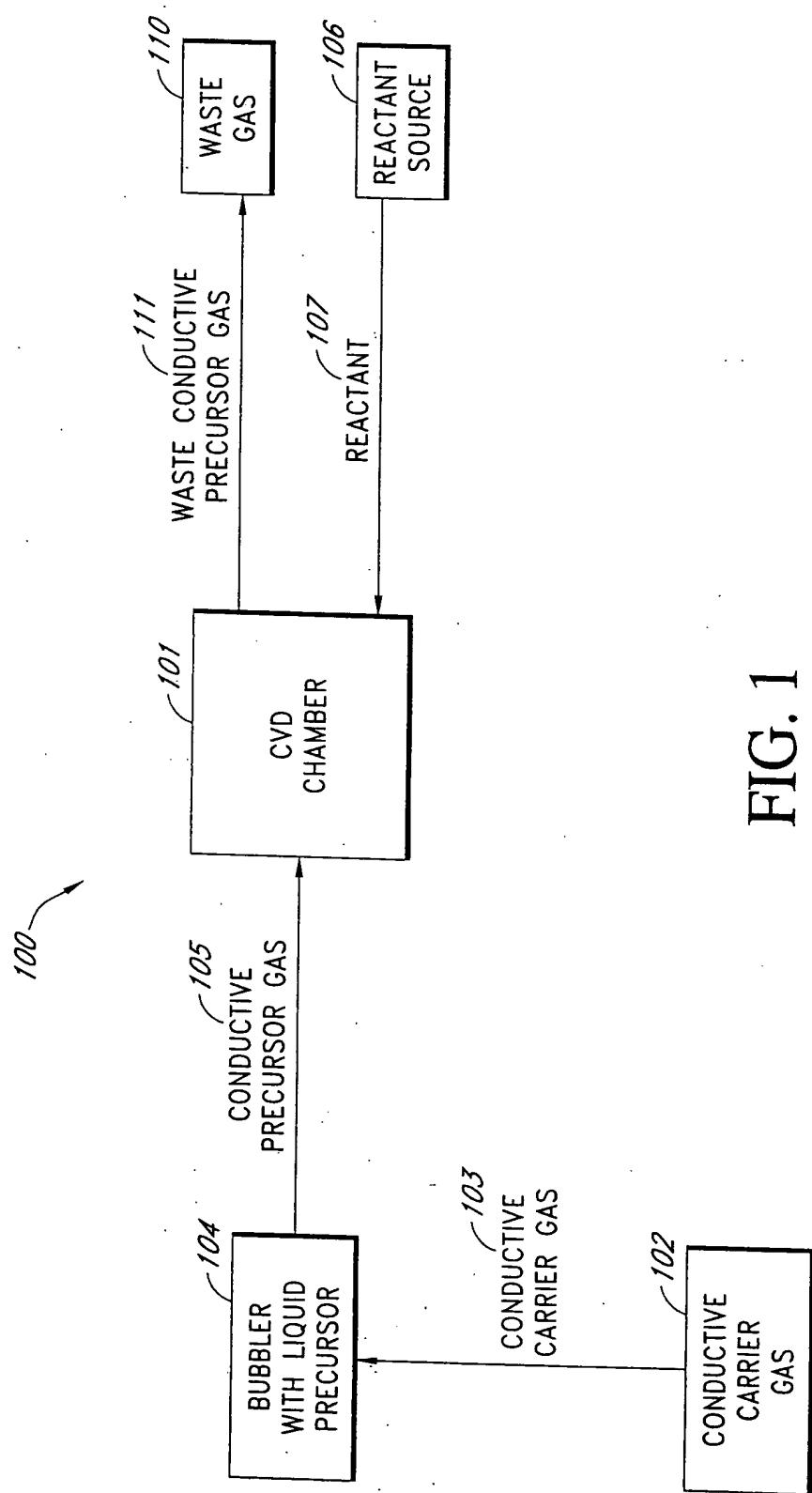


FIG. 1

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL

VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DV1CI

2/6

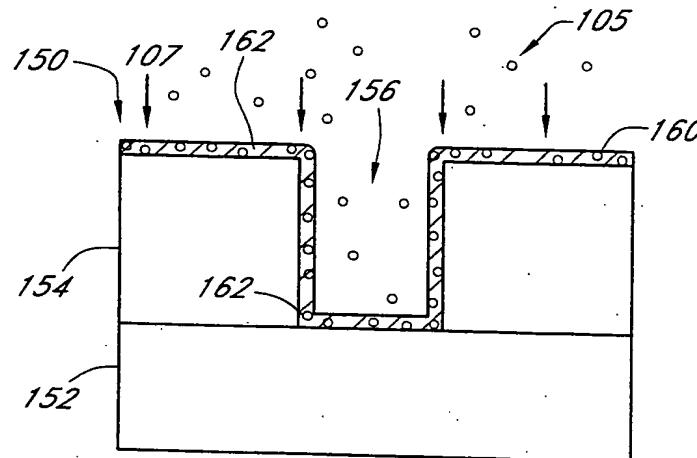


FIG. 2A

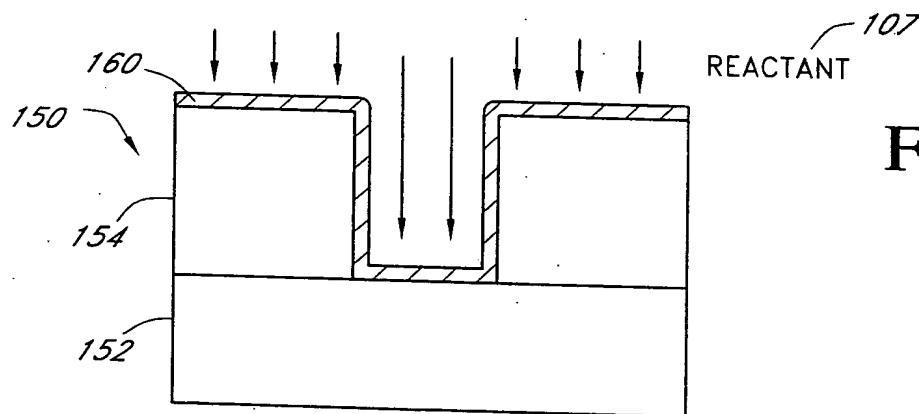


FIG. 2B

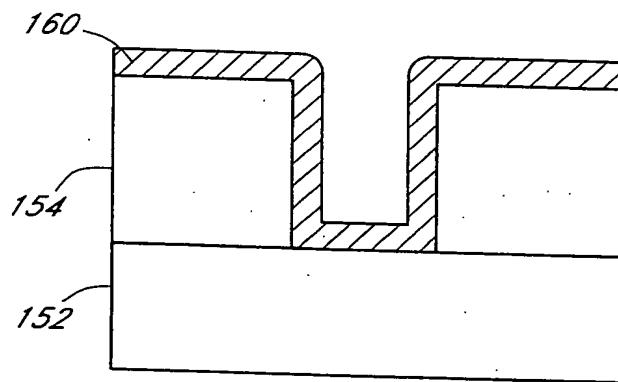


FIG. 2C

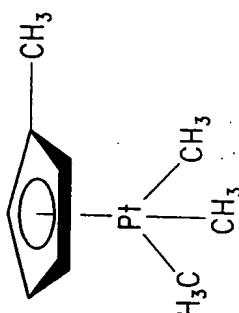
TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL VAPOR DEPOSITION

Appl. No.: Unknown

Li et al.

3/6

Pt CVD precursor



(methylcyclopentadienyl)(trimethyl)platinum

colorless crystalline - m.p. 30 C
v.p. 0.053 Torr @ 23 C

FIG. 3A

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL
VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DVIC1

4/6

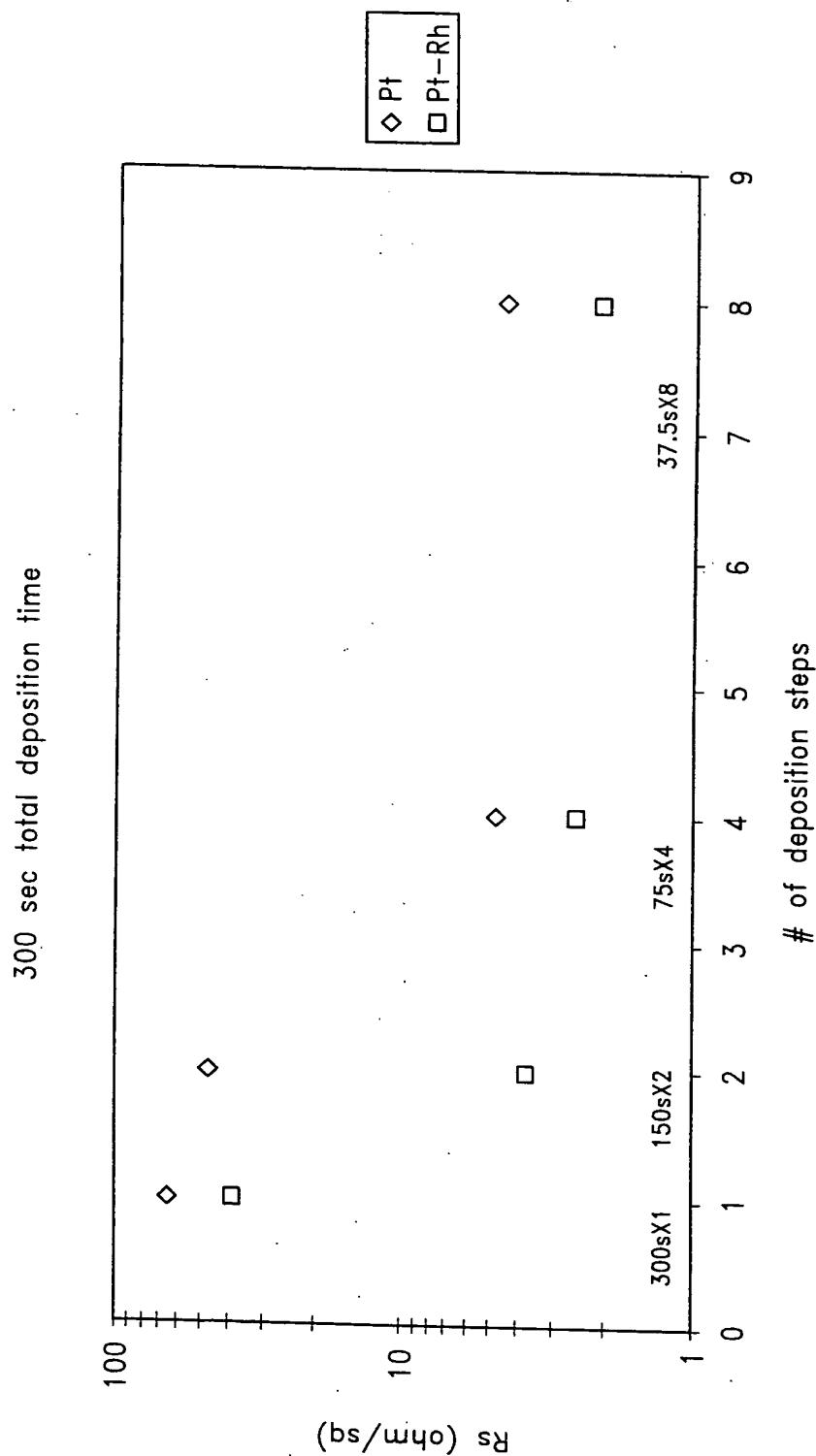


FIG. 3B

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL
VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DVICI

5/6

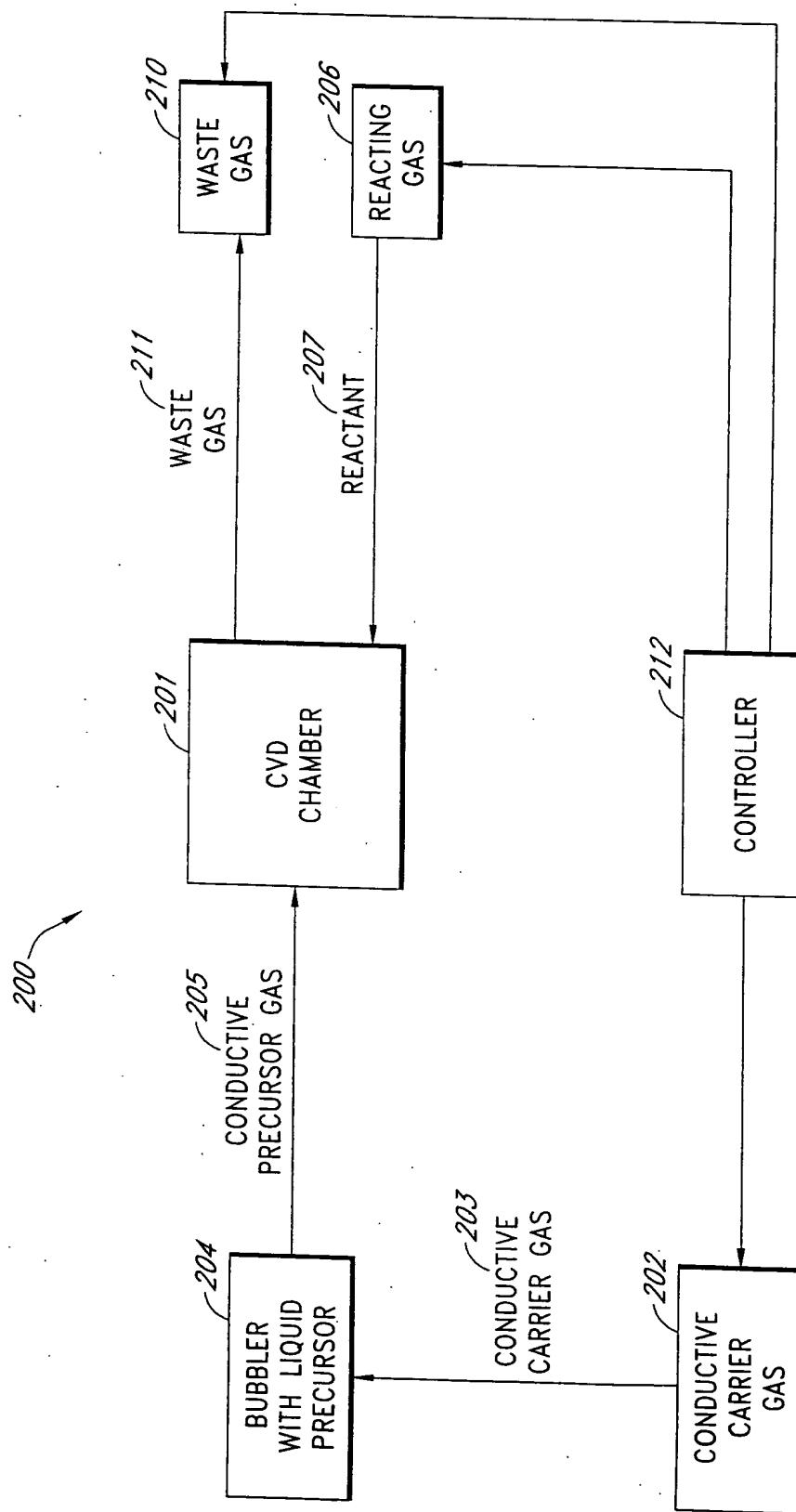


FIG. 4

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL
VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DV1C1

6/6

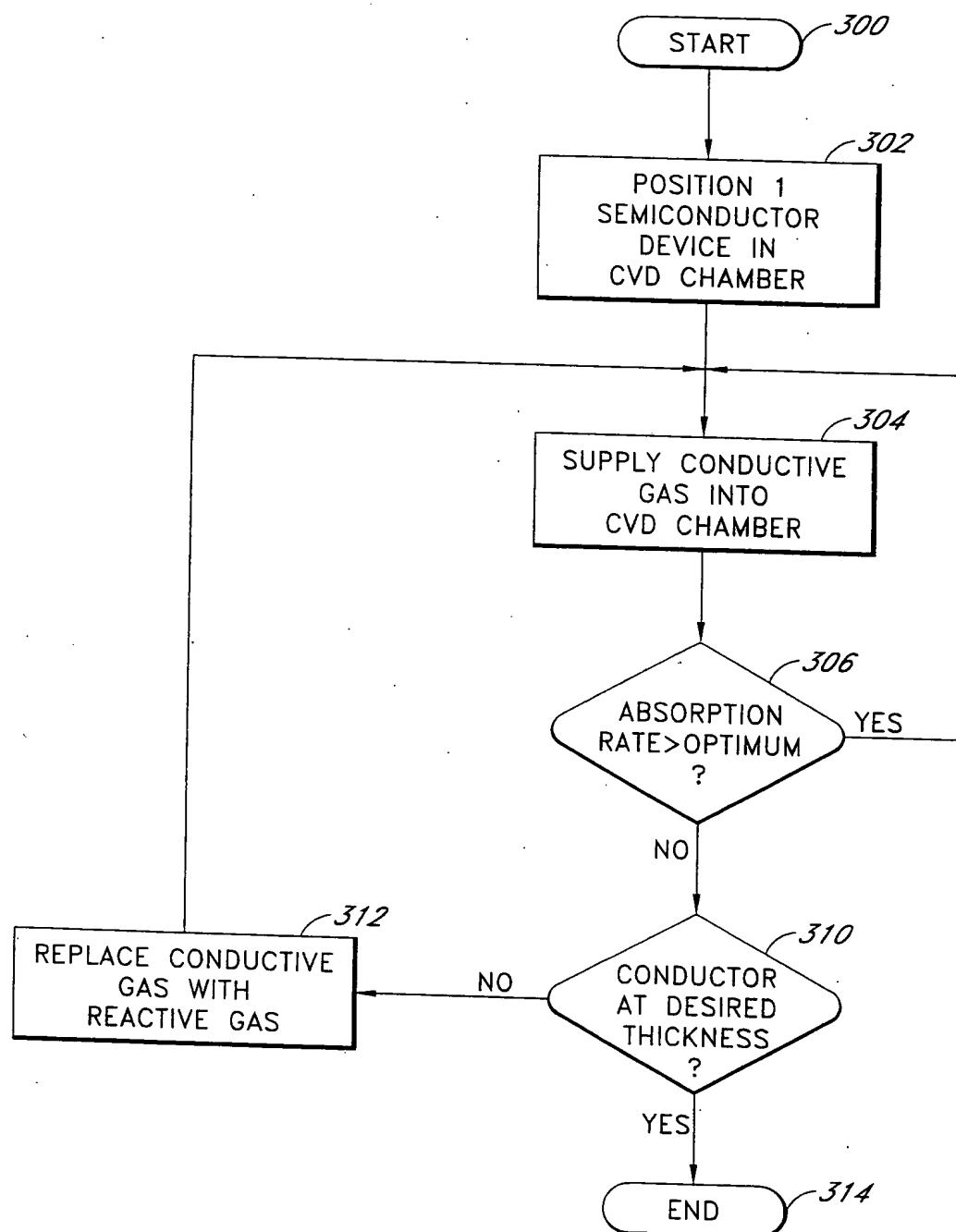


FIG. 5